Attorney Docket No.: P1031 – LAM

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Annapragada et al.) Group Art Unit: 2813
Application Serial No.: 10/712,326) Examiner: Nguyen, Thanh T
Filed: November 12, 2003)
Title: Minimizing the Loss of Barrier Materials During Photoresist Stripping))))

REQUEST FOR CONTINUED EXAMINATION, AMENDMENT AND RESPONSE TO FINAL REJECTION

MAIL STOP RCE Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir/Madam:

In response to a final rejection mailed May 10, 2007 in the above-referenced patent application, please enter and consider the following amendments and remarks in light of the attached Request for Continued Examination filed under 37 CFR §1.114.

Allowance of pending claims 1-21 in view of the following amendments and remarks is respectfully requested.

Amendments to the Claims are reflected in the listing of claims which begins on Page 2 of this paper.

Remarks begin on page 10.